

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

EXPRESS MAIL NO. EL903019195US

Applicant : Beom-Wook Lee, et al.  
Application No. : N/A  
Filed : March 7, 2002  
Title : CHEMICALLY AMPLIFIED NEGATIVE  
PHOTORESIST, AND PHOTORESIST COMPOSITION  
Docket No. : 47769/DBP/Y35

#2  
D.6.  
7-16-02

## PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231Post Office Box 7068  
Pasadena, CA 91109-7068  
March 7, 2002

Commissioner:

Applicants submit herewith a substitute specification pursuant to 37 C.F.R. § 1.125 to facilitate the prosecution of this application. The substitute specification only adds page numbering to the specification, and clarifies the claim of priority to the Korean application under the Cross Reference. The substitute specification does not contain any new matter.

## REMARKS

In view of the foregoing amendment, consideration and allowance of this application is respectfully requested.

Respectfully submitted,  
CHRISTIE, PARKER & HALE, LLP

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DBP/aam  
Enclosed: Substitute Specification